

From: Di Lu dilu@stanford.edu 
Subject: Fwd: [snf-promcommittee] New labmembership at SNF? CPD
Date: January 30, 2014 at 4:49 PM
To: snf-promcommittee@lists.stanford.edu
Cc: Uli Thumser uthumser@stanford.edu

Dear All,

Sorry for spamming this email. I want to get SNF labmembership and Uli told me that I should check with you if my wafer (they are strontium titanate single crystals) is allowed at SNF.

Thank you very much!

Best,
Di

----- Forwarded Message -----

From: "Uli Thumser" <uthumser@stanford.edu>
To: "Di Lu" <dilu@stanford.edu>
Sent: Thursday, January 30, 2014 4:31:37 PM
Subject: Re: New labmembership at SNF? CPD

<https://snf.stanford.edu/SNF/materials-and-chemicals/contamination-groups-at-snf/contamination-groups-for-controlling-process-flow-materials>

On 1/29/2014 8:03 PM, Di Lu wrote:

Do you know who I need to talk to? My wafer is just SrTiO₃.

Di

Uli Thumser <uthumser@stanford.edu> 编写 :

you should contact the Prom committee and ask if your wafer is allowed at snf

On 1/29/2014 6:48 PM, Di Lu wrote:

Hi Uli,

I guess I'm not a SNF labmember and I've never used the clean room in SNF (I only brought my sample to the cleanroom in SNC but it could be quite different).

Best,
Di

----- Original Message -----

From: "Uli Thumser" <uthumser@stanford.edu>
To: "Di Lu" <dilu@stanford.edu>
Sent: Wednesday, January 29, 2014 6:01:41 PM
Subject: Re: New labmembership at SNF? CPD

Hi Di,

Are you a SNF labmember already and is your sample allowed in our clean room?

Uli

On 1/28/2014 6:04 PM, Nancy Latta wrote:

Hi Di,

I am going to pass you off to Uli who knows all about the cpd. I have cc'd her on this message.....

On 1/28/2014 5:15 PM, Di Lu wrote:

Hello Nancy,

My name is Di Lu, a grad student in Stanford and I'm working in professor Harold Hwang's lab in GLAM building. We are actually planning to use the critical point dryer (CPD) in SNF for some...

planning to use the critical point dryer (CPD) in SNF for our new project. We want to fabricate some ferromagnetic micro- or nano-resonators, and a CPD will help us reduce the surface tension effects induced by the normal drying process of the solution. Do we need to have a discussion about this?

Please let me know if you need more information.

Thanks,
Di



uthumser.vcf

snf-promcommittee mailing list

snf-promcommittee@lists.stanford.edu

<https://mailman.stanford.edu/mailman/listinfo/snf-promcommittee>